

Industrial Instruments General Catalogue

2014



The highly cost-effective SMZ series offer outstanding optical performance, flexible system expandibility, and superb operability.

Parallel Optics Type							
	SMZ25	SMZ18	SMZ1000	SMZ800			
Zoom Ratio	25 : 1	18 : 1	10 : 1	6.3 : 1			
Zoom Range	0.63-15.75×	0.75-13.5×	0.8-8×	1–6.3×			
Total Magnification*1 (Standard combination*2)	3.15-945× (6.3-157.5×)	3.75-810× (7.5-135×)	4-480× (8-80×)	5–378× (10–63×)			
W.D.*3	60mm	60mm	70mm	78mm			
Camera	V	V	V				
`				: Available / — : Not available			

	Greenough Type								
	SMZ745		SMZ445		SM-5				
	SMZ745T	SMZ660	SMZ460	SMZ	SM-6				
Zoom Ratio	7.5 : 1	6.3 : 1	4.4:1 4.3:1	5:1	_				
Zoom Range	0.67–5×	0.8-5×	0.8 - 0.7 - 3.5× 3×	0.8-4×	_				
Total Magnification* ¹ (Standard combination* ²)	3.35-300× (6.7-50×)	4-300× (8-50×)	4–70× 3.5–60× (8–35×) (7–30×)	4–120× (8–40×)	10-60× (20×)				
W.D.*3	115mm	115mm	100mm	77.5mm	100mm				
Camera	✓ (SMZ745T only)		<u> </u>						
				✓ : Avai	lable / — : Not available				

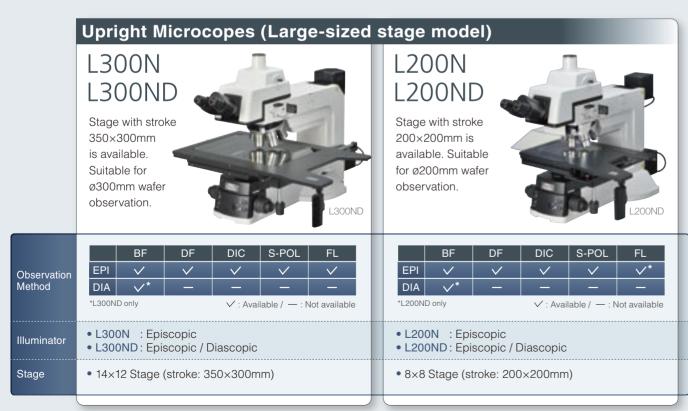
Please refer to individual product brochures for further details.

Nikon's Industrial Microscopes utilize the CFI60-2 optical systems, highly evaluated for its unique concept of high NA combined with long W.D.



BF: Brightfield DF: Darkfield DIC: Differential Interference Contrast FL: Flourescence POL: Polarizing 2-Beam: Two-Beam Interferometry Ph-C: Phase-Contrast

Stage



BF: Brightfield DF: Darkfield DIC: Differential Interference Contrast S-POL: Simple Polarizing FL: Flourescence

Inverted Metallurgical Microscopes

MA200

With its unique, solid-box structure. the MA200 offers high stability. durability, and a smaller footprint than conventional models.



MA100 **MA100L**

MA100 and MA100L are compact, inverted microscopes designed for brightfield and simple polarizing observations.



		BF	DF	DIC	S-POL	FL		BF	DF	DIC	S-POL	FL
Observation	EPI	V	V	V	V	V	EPI	V	-	_	V	_
Method	DIA V V V —					✓ : Available / — : Not availa						
	✓ : Available / — : Not available											
Illuminator	Episcopic / Diascopic					• Epis	scopic					
Stage	MA2-SR Mechanical Stage (stroke 50×50mm)					• MA-	-SP Plan	Stage	Ü	`	0×50mm) 126×80mm)	

BF: Brightfield DF: Darkfield DIC: Differential Interference Contrast S-POL: Simple Polarizing FL: Flourescence

Polarizing Microscopes

LV100NPOL Ci POL

High quality polarizing microscopes with superb optical performance that accommodate various observation needs.



Multi-purpose Zoom Microscopes

AZ100 **AZ100M**

Multizoom AZ100 and AZ100M combine the advantages of stereoscopi and metallographic microscopes.



		BF	POL			BF	DF	DIC	S-POL	FL
ion	EPI	V	✓		EPI	V	_	V	_	V
	DIA	V	✓		DIA	V	V	V	V	_
	√ : Available / — : Not available							✓ : Avai	lable / — : N	Not availa
or	• Epis	copic/ Diascopic			• Epis	scopic/ [Diascopic			
	LV100NPOL: High precision rotating stage for polarizing observation			6×6 Stage (stroke 150×150mm) for e 6×4 Stage (stroke 150×100mm) for d				, ,		
	• Ci P	OL : Rotating stage	with stage clamp						•	•

BF: Brightfield POL: Polarizing DF: Darkfield DIC: Differential Interference Contrast S-POL: Simple Polarizing FL: Flourescence

Please refer to individual product brochures for further details.

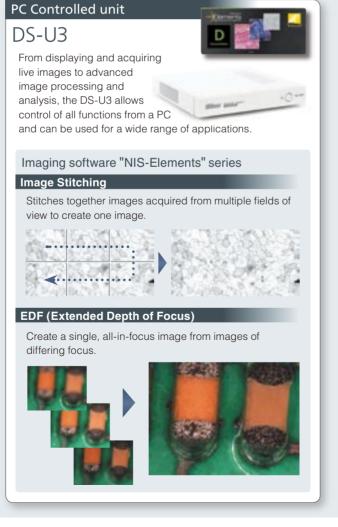
Stage

A range of features are available to suit every observation sample, such as color /monochromatic, cooled / non-cooled, 5.0 / 2.0 megapixel CCD. The Digital Sight (DS) camera system allows for numerous combinations with camera heads and stand-alone or PC-based control units.



^{*}See the "Digital Sight series" catalog for other camera heads.





Digital Microscopes

ShuttlePix P-400Rv

An all-new, one-of-a-kind digital microscope that can either be portable to accommodate any sample size or docked on a stand to take high-magnification images and perform various measurements.



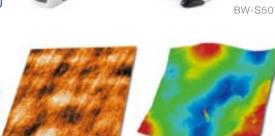
Super High Vertical Resolution Non-Contact 3D Surface Profilers

BW-D500 Series/ BW-S500 Series

Nikon's proprietary scanning-type optical interference measurement technology achives 1pm height resolution. Nikon offers variety application, lustrous surfaces, such as silicon wafer, glass and metallic deposition surfaces.

	High Speed Model BW-D500 Series		solution Model 00 Series			
Height Resolution (algorithm)		1pm				
Step Height Measurement Reproducibility	σ: 8nm (8μm Step height measurement)					
Number of Pixels	510×510	2,046×2,046	1,022×1,022			
Height Measurement Time	4 s (10µm scan)	38 s (10µm scan)	16 s (10µm scan)			
Field of view	< 2,015×2,015µm*	< 4,458×4,448µm*				

^{*} The range can be extended by changing the relay lens or by stitching.



Polished ceramic surface

Metal Etching Surface

Lens

Glass



Objective Lenses

CFI60-2 / CFI60 / CF&IC

Nikon's CFI60-2/CFI60/CF&IC optical systems are highly evaluated for its unique concept of high NA combined with long working distance. These lenses have further evolved to achieve the apex in long working distance, correct chromatic abserration, and optimized lens weight.







BF: Brightfield DF: Darkfield POL: Polarizing S-POL: Simple Polarizing DIC: Differential Interference Contrast UV-FL: UV Flourescence FL: EPI Flourescence

	Model	Magnification	NA	W.D. (mm)	BF	DF	POL	S-POL	DIC	UV-FL	FL
	T Plan EPI	1×	0.03	3.8	→ MF			_	_	_	_
	Plan (Semi-apochromat)	2.5×	0.075	6.5	·····	····	···-				
	TU Plan Fluor EPI	5×	0.15	23.5	~			V	∨ A	V	V
	Universal Plan Fluor (Semi-apochromat)	10×	0.3	17.5	~				∨ A	V	V
	(2.2 5)	20×	0.45	4.5	~			~	∨ A	V	V
		50×	0.8	1.0	V		_		∨ A	~	V
		100×	0.9	1.0	V	_		V	∨ A	V	V
	TU Plan Apo EPI	50×	0.8	2.0	V				∨ A		V
	Universal Plan Apo (Apochromat)	100×	0.9	2.0		ļ—			✓ A		<u> </u>
		150×	0.9	1.5	V	_	_	V	✓ A		
	TU Plan Fluor EPI P	5×	0.15	23.5					✓ A		
	Polarizing Universal Plan Fluor (Semi-apochromat)	10×	0.3	17.5					✓ A		
		20×	0.45	4.5	<u>/</u>	ļ -	····×	Y	∨ A	· · · · · · · · · · · · · · · · · · ·	
		50×	0.8	1.0	Y				✓ A	· · · · · ·	·····×
		100×	0.9	1.0	V		V	V	∨ A	V	<u> </u>
	TU Plan EPI ELWD	20×	0.4	19.0		ļ -			∨ B	ļ .	
CEL. 2	Long Working Distance Universal Plan (Semi-apochromat)	50×	0.6	11.0	Y	ļ .	ļ <u> —</u>		∨ B	ļ .	<u></u>
CFI60-2		100×	0.8	4.5					∨B		
NEW	T Plan EPI SLWD	10×	0.2	37.0 30.0		ļ <u>-</u>	-	ļ <u>-</u>	ļ <u>. </u>	ļ <u>-</u>	
NEW _	Super Long Working Distance Plan (Semi-apochromat)	20×				ļ <u>-</u>	ļ <u>-</u>	ļ <u>-</u>	<u>-</u>	ļ <u>.</u>	·····
	(Genii-apocnionial)	50× 100×	0.4	22.0 10.0		ļ <u>.</u>	<u>-</u>		····	····	Y
				18.0	\ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \						
	TU Plan Fluor BD	5× 10×	0.15 0.3	15.0				Y	✓ A ✓ A		Y
	Universal Plan Fluor (Semi-apochromat)	20×	0.45	4.5			<u></u>		✓ A		····
		50×	0.45	1.0		<u>×</u>	<u>-</u>	<u>Y</u>	✓ A	Y	<u>Y</u>
		100×	0.9	1.0	· · · · · · · · · · · · · · · · · · ·	· · · · · · · · · · · · · · · · · · ·	····Ξ····		✓ A	····×	<u>×</u>
	TUDI A DD	50×	0.8	2.0	V	~			✓ A		
	TU Plan Apo BD Universal Plan Apo (Apochromat)	100×	0.9	2.0	·····×		_		✓ A	ļ <u>-</u>	
	Oniversal Flam Apo (Apochionial)	150×	0.9	1.5	<u>×</u>	<u>×</u>		<u>×</u>	✓ A	····	<u>×</u>
	TU Plan BD ELWD	20×	0.4	19.0	~	×		· /	∨ B		V
	Long Working Distance Universal plan	50×	0.6	11.0		×	l _		∨ B		
	(Semi-apochromat)	100×	0.8	4.5	~	~			✓ B		~
	L Plan EPI (Achromat)	40×	0.65	1.0	· /		_		_		
	LU Plan Apo EPI / Universal Plan Apo (Apochromat)	150×	0.95	0.3	V	_	_		∨ A	_	V
	LU Plan Apo BD	100×	0.9	0.51	V	~		V	√ A		<u> </u>
CFI ₆₀	Universal Plan Apo (Apochromat)	150×	0.9	0.42	V	V		V	∨ A		<u> </u>
CFI60	L Plan EPI CR	20×	0.45	10.9-10.0	~			_	_	_	~
	LCD Substrate Inspection Plan (Achromat)	50×	0.7	3.9-3.0	~					_	V
	*Offers valid while supplies last	100×	0.85	1.2-0.85	~						V
		100×	0.85	1.3-0.95	~				_	_	V
	CF IC EPI Plan	2.5×	0.075	8.8							V
	Plan (achromat)	5×	0.13	22.5	~					_	V
	,	10×	0.3	16.5	~					_	V
		20×	0.46	3.1	~						V
		50×	0.8	0.54	~						V
		100×	0.95	0.3	~	_	_	_	_	_	V
	CF IC EPI Plan Apo	50×	0.95	0.4	~						V
	Plan Apo (Apochromat)	100×	0.95	0.3							V
		150×	0.95	0.2	V	_					V
	CF IC EPI Plan ELWD	20×	0.4	11	~						V
CF&IC	Long Working Distance Plan (Achromat)	50×	0.55	8.7	V						V
		100×	0.8	2	V	_	_		_	_	V
	CF IC EPI Plan SLWD	10×	0.21	20.3	Y	ļ -	ļ -		ļ -	ļ -	
	Super Long Working Distance Plan (Achromat)	20×	0.35	20.5		ļ <u> —</u>		ļ <u> —</u>		ļ <u> —</u>	
		50×	0.45	13.8							
		100×	0.73	4.7	V	_	_		_	_	V
	CF IC EPI Plan TI	2.5×	0.075	10.3							
	DIC Plan	5×	0.13	9.3	V		_	_	_	_	_
	CF IC EPI Plan DI	10×	0.3	7.4	Y	ļ <u>-</u>		ļ <u>-</u>		ļ <u>-</u>	
	DIC Plan	20×	0.4	4.7	Y	ļ 	ļ 	ļ <u> —</u>	ļ 	ļ <u> —</u>	
		50×	0.55	3.4	Y	ļ <u> —</u>		ļ	-	ļ <u> —</u>	
		100×	0.7	2.0	V	_	_	_	_	_	_

Near-infrared Objective Lenses

NIR / NIR-C

Achieves high transmission of 90% or more at visible range and 1,064 nm. Significantly improved machining accuracy at a small size with low power. Suitable for Semiconductor and LCD by laser repair.

	Model	Magnification	NA	W.D. (mm)	Wave Length (n.m)	Parfocal Distance (mm)
NUO	NIR,*1	20×	0.40	25.0	1,064/532	95
NIR &	Near-Infrared Plan	50×	0.42	20.0	1,064/532	95
NIR-C	NIR-C,*1	20×	0.40	24.0 *2	1,064/532	95*3
14111	Near-Infrared Plan (glass thickness correction range 0.3-1.1mm)	50×	0.42	19.0 •2	1,064/532	95.3

^{*1:} Please ask us regarding transmission outside of vision range and 1064nm, *2: W.D. is measured from the object surface with 1.1mm thick cover glass.

For Incorporation into Microscopes

Modular Focusing Units

IM-4, LV-IM/LV-IMA, LV-FM/LV-FMA

Suitable for incorporating into systems, these focusing units enable the mounting of a universal illuminator and a motorized nosepiece.

	IM-4	LV-IM/LV-IMA	LV-FM/LV-FMA
Туре	Manual	Manual / Motorized	Manual / Motorized
Vertical Stroke	30mm	30/20mm	30/20mm



Dynamic Auto-Focus Unit

LV-DAF

Hybrid Auto-focus features a wide focus range and fast tracking ability.

A wide range of observation methods are supported, including brightfield, darkfield, and DIC. Reflective and transparent samples can both be observed.

Detection System	Split Projection System/ Contrast Detection System						
AF Light Source	Light Source Near Infrared LED (λ=770nm)						
Focal Time	within 0.7 sec (Obj. lens: 20×, Distance from focal position: 200μm)						
Observation	Brightfield, Darkfield, Polarizing, DIC						



Compact Reflected Microscopes

CM Series

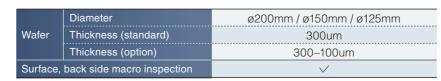
Ultra-compact reflected microscopes designed for integration into production lines to observe on monitors.



	CM-5A	CM-10A/CM-10L	CM-20A/CM-20L	CM-30A/CM-30L				
Camera Mount	C-mount (ENG-mount possible with option)							
Tube Lens Magnification	<u> </u>	1x	0.5×	1×				
Compatible Objectives	A series: CF	IC EPI Plan objectives / L se	eries: CFI60-2/ CFI60 EPI Pla	n objectives				
Illumination Optical System	k	Koehler illumination (high-quality telecentric illumination)						
Attachment Surfaces		3	4					

Wafer Loaders

Nikon's proprietary technology ensures reliable loading of ultra-thin 100µm wafers. The NWL 200 series achieve highly reliable loading, suitable for inspection of next-generation semiconductors.







Please refer to individual product brochures for further details. Please refer to individual product brochures for further details.

^{✓ :} Available / — : Not available *A: Set prism position at A / B: Set prism position at B

^{*3:} Because of a shift in parfocal position when used in conjunction with cover-less objective lens, parfocal distance is corrected by correction rings and washers.

Wide variety of stage strokes and magnifications are available for various customer requirements.

Main Body (Type / Stage Stroke)



iNEXIV VMA-4540



High Accuracy Type
VMR-H
Model VMR-H3030
NEXIV VMR-H3030

Туре	Wide	FOV	Standard								
XY Stroke (mm)	250×200	450×400	150×150	300×200	450×400	650×550	1000×800	1200×720	300×300		
Wide FOV Head	V	V		✓	V	✓					
Stardard Head			V	V	V	V	V	V	V		
High-Magnification Head			V	V	~	~	\	\	V		
Z-axis Stroke (mm)	200	200	150	200	200	200	150	150	150		
Max. guaranteed loading capacity (kg)	15	20	20	20	40	50	40	40	30		
Max. permissible errors (μm) Eux, Mpe:	1.5+4L/1000	2+6L/1000	1.5+4L/1000	1.2+4L/1000	1.2+4L/1000	1.2+4L/1000	2+4L/1000	2.2+4L/1000	0.6+2L/1000		
Max. permissible errors in Z axis (μm) Euz, Mpe:*1	1.5+L/150	3+L/100	1.5+L/150	1.2+5L/1000	1.2+5L/1000	1.2+5L/1000	1.5+L/150	1.5+L/150	0.9+L/150		

L = Length in mm *1: with Laser AF or Touch Probing

Zoom Heads

Type A

FOV

Wide FOV and long working

distance enables comfortable operation. Laser AF and Touch

Wide FOV Head Type A Stardard Head Type 1

Probe can be attached as optional accessories.

*Touch Probe is an option only for VMA series.

Type 2

Type 3

Type 4

Type 1-4

Equipped with top, bottom, and oblique ring

lights with adjustable angles. TTL (Through The Lens) Laser AF is a standard tool that can scan surfaces at 1000 points/second.

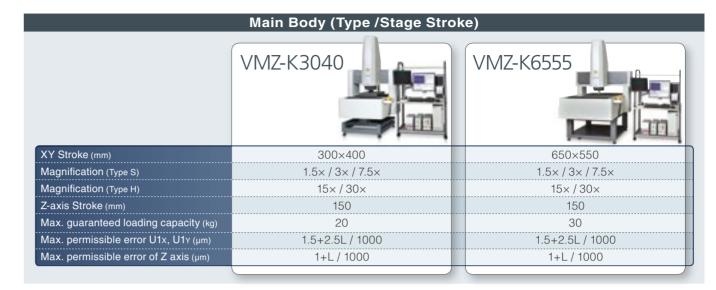
Type TZ

Equipped with 1-120x ultra high zoom ratio with 8 steps. Suitable for





Simultaneous wide-area height measurements with confocal optics and 2D measurement with 15x brightfield zoom optics.



							Zoo	m H	eads									
FOV	W(mm)× D(mm)	8 6	4 3	2.0 1.5	1.6 1.2	1.26 0.95	1.00 0.75	0.8 0.6	0.63 0.47	0.53 0.40	0.4 0.3	0.30 0.23	0.27 0.20	0.20 0.15	0.11 0.08	0.100 0.074	0.05 0.04	W.D.
Type S	1.5×	•	-	-			-			_								24mn
	3×		•	-			-			-			-					24mn
	7.5×				•			-9			-9			-9				5mr
Туре Н	15×					9—		-	-			-9						20mr
	30×								•		•	-				-	—	5mr
							• Con	focal O	ptics	Brigh	tfield O	ptics	Both	brightfie	ld and 3	3D image	es are a	vailable

Confocal NEXIV incorporates confocal optics for fast and accurate evaluation of fine three-dimensional geometries.

Confocal Optics are designed for wide FOV height measurement.





Thin Transparent Samples (Metal Surface Film / Semiconductor Resist

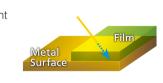
High Contrast and Multileveled Sample (PCBs)

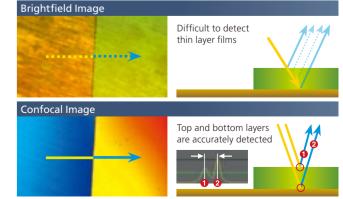
Brightfield observation can sometimes be difficult due to blurred lines along sample structure. These lines can be clearly observed and measured using Confocal optics.





Top layers of both thin transparent film and metal surface can be easily detected using Confocal optics.







Please refer to individual product brochures for further details. Please refer to individual product brochures for further details.

Measuring Microscopes

Focused on high-precision and easy operability, a wide range of MM-products are available.



Basic Model MM-400

Large-Stage Model
MM-800
Second !
20
0000

	50×50mm / 5kg	V	V	✓
	100×100mm / 15kg	<u> </u>		
Stage Size/ Loading	150×100mm / 15kg	_	V	
Capacity	200×150mm / 20kg	_	_	<u> </u>
	250×150mm / 20kg	_	_	<u> </u>
	300×200mm / 20kg	_		
Max. Workpie	ece Height	110mm	150mm	200mm
Optical	Monocular	~	✓	_
Head	Binocular	_	V	✓
X-Y-Z	2-axis	~	✓	✓
Λ-1-Z	3-axis	_	V	✓
CCD		~ *	<u></u>	✓
Obj. Magnification		1×/3×/5×/10×	1×/3×/5×/10×	/20×/50×/100×

*For simple video head only

✓ : Available / — : Not available

MM Type

With Nikon's optical technology and newly developed stages, high-precision measurement can be achieved.



Universal Type

dimensional measurement and various observation methods.



Newly Developed High-Precision Stages

The coarse/fine changeover lever and the RESET and SEND buttons are located near the X- and Y-axis knobs.





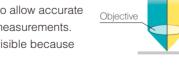


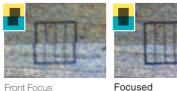


Y-axis Knob

Focusing Aid (FA)

The newly developed Split-Prism FA delivers sharp patterns to allow accurate focusing during Z-axis measurements. FA patterns are clearly visible because they are split vertically







Rear Focus

Profile Projectors

Nikon's profile projectors apply the principles of optics to the inspection of manufactured parts by projecting magnified silhouettes on a screen.



Large-Screen Model
V-20B
THE CO-
52
(1)
Acres 10
ALC: N



	50×50mm / 5kg	✓		V	_	
	100×100mm / 15kg	✓		_		
Stage Size/ Loading	150×100mm / 15kg	~		V	_	
Capacity	200×150mm / 20kg	✓		V	_	
	250×150mm / 20kg	✓		✓	_	
	225×100mm / 30kg	<u> </u>		_	✓	
Max. Workpiece Height		100mm*²		150mm	250mm	
Screen		305mm		500mm	600mm	
Image		Erect		Inverted	Inverted	
Projection	Magnification	5×/10×/20×/25×/50×/100×/200×		5×/10×/20×/50×/100×	5×/10×/20×/50×/100×	
Lens	FOV (with 10× lens)*1	30.5mm		50mm	60mm	
Digital Protractor		✓		V	_	
Digital Counter		✓		V	√(External)	

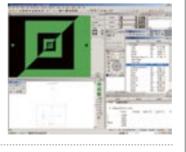
*1: Actual FOV = Effective diameter of screen / Lens magnification *2: Maximum sample height is 70mm when 200×150mm stage is installed. ✓ : Available / — : Not available

Data Processing Systems for Measuring Microscopes and Profile Projectors

Data Processing Software



Provides the user with various advanced measurements and processing functions. Automated edge detection with sub-pixel processing enables more precise and repeatable measurements.



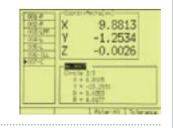
Connected with profile projector, data processing functions only

Data Processor

DP-E1



Effectively used with a measuring microscope /profile projector, it quickly calculates and processes measurement data. Feature Oriented Operation of the DP-E1 allows the user to conduct measurements with the graphics, providing a seamless measuring environment.



Connected with profile projector, retrofit counter and DP units are required.

Metrology Software

U-DP



The browsered geometric dimensioning software can be effortlessy connected via Ethernet or Wifi to electronic devices. Interactive navigation enables immediate operation, while the simple screen layout enables easy measurement results confirmation.

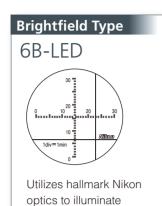


[Operating environment] OS: Windows®XP, Windows®7

Required memory: 2GB (min.) Recommended browsers: Windows® Internet Explorer Ver6.0.2.9 or later

Autocollimators

Autocollimator is an easy-to-use but precise metrology instrument for angularity, parallelism, perpendicularity, straightness of precision components machine guideway and many other applications.



surface details.

Darkfield Type 6D-LED



Optimal for measuring small, flat mirrors.



Observation Method
Readout System
Measuring Range
Minimum Danga

6B-LED: Brightfield, 6D-LED: Darkfield Adjustment in viewfield and reading on micrometer 30 minutes of arc (both vertical and horizontal axes) 0.5 seconds of arc

Plane Mirror C

Both sides are perfectly parallel, permitting its use as a reference for non-reflective surface. Also useful for measuring extremely small angles where a smaller mirror is desirable. *Wooden case provided.



Outer Diameter	30mm
Thickness	12mm
Parallelism	2 seconds of arc

LED Illuminator AC-L1

LED illumination unit for retrofitting onto Autocollimator 6B/6D illumination unit.



Power Source

AA batteries×2, AC adaptor

DIGIMICRO

With built-in photoelectric digital length measuring systems, DIGIMICRO offers flawless contact measuments of dimension, thickness, and depth.





Stand MS-21



Mainunit MF-501 + Counter MFC-101 + Stand MS-11C

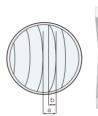


Optical Flat / Optical Parallel / Standard 300mm Scale

Optical Flat

The optical flat is used to check the flatness level of a surface provided with mirror-smooth finish.

Flatness level can be measured by observing inteference fringes by placing the optical flat in contact with the workpiece.





Diameter	Glass (ø60mm)	Glass (ø130mm)
Thickness	15mm	27mm
Flatness	0.1µm	0.1µm

Optical Parallel

Both planes of the optical parallel have been precisely finished flat and parallel.

It is used to check the flatness and parallel levels of

a workpiece by observing intereference fringes by placing the optical parallel in contact with the workpiece.

Diameter	30mm
Thickness	12mm / 12.12mm / 12.25mm / 12.37mm
Flatness	within 0.1µm
Parallelism	within 0.2μm

^{*}Optical flats and parallels with greater precision are available by custom orders.

Standard 300mm Scale

Gauges stage travel accuracy up to 300mm. Both 10mminterval sensor patterns and calibrations are provided. Made of low heat-expansion glass, for minimizing influence of heat.

*Within 1µm against compensation values.

Please refer to individual product brochures for further details. Please refer to individual product brochures for further details. 15

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TO ENSURE CORRECT USAGE, READ THE CORRESPONDING MANUALS CAREFULLY BEFORE USING THE EQUIPMENT.



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